Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

- 1-11. (Canceled)
- 12. (Currently Amended) The system of claim 11 A micromachined filter system, comprising:

 a micro-device having a plurality of micromachined layers formed over a substrate; and

 a micromachined filter integrated in at least one of the micromachined layers, wherein each layer that comprises the micromachined filter comprises consists of a series of substantially parallel beams.
- 13. (Currently Amended) The system of claim 11 A micromachined filter system, comprising:

 a micro-device having a plurality of micromachined layers formed over a substrate; and

 a micromachined filter integrated in at least one of the micromachined layers, wherein each layer that comprises the micromachined filter comprises consists of a series of substantially parallel columns.
- 14. (Currently Amended) The system of claim 11 12, wherein the micromachined filter comprises:
- a first series of substantially parallel beams formed in a first micromachined layer; and
- a second series of substantially parallel beams formed in a second micromachined layer, the first and second series of beams being substantially parallel and at least partially offset to one another.
- 15. (Currently Amended) The system of claim 11 12, wherein the micromachined filter comprises:

a first series of substantially parallel beams formed in a first micromachined layer; and

a second series of substantially parallel beams <u>formed in a second</u>

<u>micromachined layer</u>, the first and second series of beams <u>being extending in non-parallel</u>

directions with <u>respect</u> to one another.

16-18. (Canceled)

- 19. (Currently Amended) The filter of claim 18 A filter comprising a micromachined layer of polysilicon, wherein the micromachined layer of polysilicon comprises consists of a series of substantially parallel beams.
- 20. (Currently Amended) The filter of claim 18 A filter comprising a micromachined layer of polysilicon, wherein the micromachined layer of polysilicon comprises consists of a series of substantially parallel columns.
- 21. (Currently Amended) The filter of claim 18 19, wherein the micromachined layer of polysilicon comprises:
- a first series of substantially parallel beams formed in a first micromachined layer; and
- a second series of substantially parallel beams <u>formed in a second</u>

 <u>micromachined layer</u>, the first and second series of beams being substantially parallel and at least partially offset to one another.
- 22. (Currently Amended) The filter of claim 18 19, wherein the micromachined layer of polysilicon comprises:
- a first series of substantially parallel beams formed in a first micromachined layer; and

a second series of substantially parallel beams <u>formed in a second micromachined</u>

<u>layer</u>, the first and second series of beams <u>being extending in non-parallel directions with</u>

<u>respect</u> to one another.

- 23-32. (Canceled)
- 33. (New) The system of claim 14, wherein the first and second micromachined layers are micromachined polysilicon layers.
- 34. (New) The system of claim 15, wherein the first and second micromachined layers are micromachined polysilicon layers.
- 35. (New) The filter of claim 21, wherein the first and second micromachined layers are micromachined polysilicon layers.
- 36. (New) The filter of claim 22, wherein the first and second micromachined layers are micromachined polysilicon layers.
- 37. (New) The system of claim 12, wherein the at least one of the micromachined layers is a micromachined polysilicon layer.
- 38. (New) The system of claim 13, wherein the at least one of the micromachined layers is a micromachined polysilicon layer.
- 39. (New) The system of claim 12, wherein each of the beams has a width of at least about 1 micron.
- 40. (New) The filter of claim 19, wherein each of the beams has a width of at least about 1 micron.
- 41. (New) The system of claim 12, wherein the micro-device has a fluid inlet through the substrate and the micromachined filter is situated downstream of the fluid inlet.
- 42. (New) The system of claim 13, wherein the micro-device has a fluid inlet through the substrate and the micromachined filter is situated downstream of the fluid inlet.

- 43. (New) The system of claim 41, wherein the micromachined filter is situated over the fluid inlet.
- 44. (New) The system of claim 42, wherein the micromachined filter is situated over the fluid inlet.